



# Sealed-Cell Photo-DSC: A New Tool for Process Safety Evaluation of Photochemical Processes

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# Outline

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- Background: Application of DSC to Photochemical Systems
- Design/Development of a Photo-DSC method
- Proof-of-Concept Data
- Future Direction

But first.... a shameless plug!

Merck currently has a job opening (Assoc. Principal Scientist) for a process safety chemist, posting is open through May 16

# Photochemistry

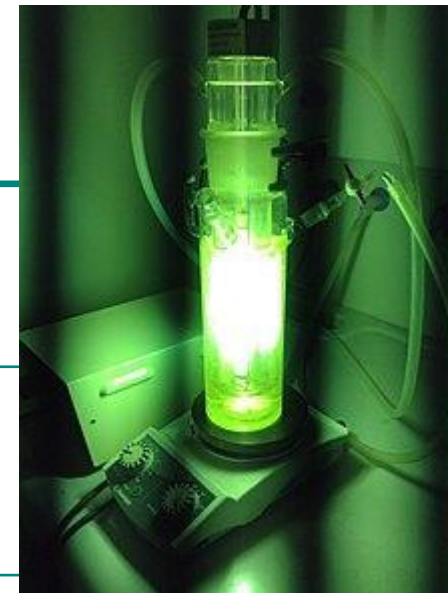
Photochemistry is becoming a key element of the pharma chemistry toolbox

- Novel reactivity, milder conditions, higher selectivity

Photons excite starting materials or transition state

- Can enable new reaction mechanisms (including degradation pathways!)

We cannot keep doing our thermal hazard workflows in the dark!



# What is DSC?

Used to assess processes for overheat upset scenario

- Jacket runaway scenario or loss of cooling in exothermic reaction

DSC (differential scanning calorimetry) measures the heat flow of a sample vs. a reference when temperature ramps up

- Low sample requirement (~2-5 mg)
- First-pass screening to determine further testing needs

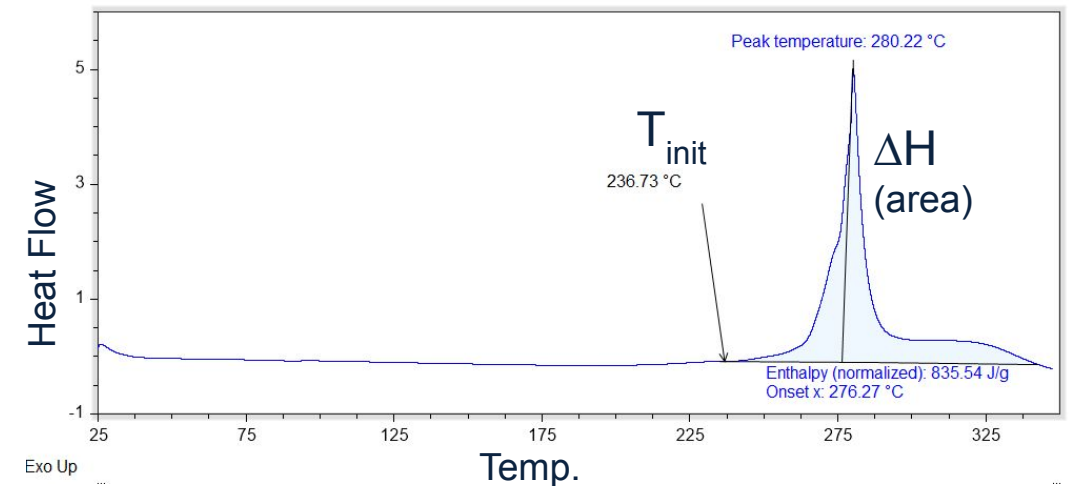
Standard testing:

- Both raw materials and process streams
- Typically scan up to ~350°C
- Jacket runaway scenario can reach up to ~180°C

For reactions with organic solvents, the sample must be sealed in a non-reactive pan for analysis (e.g., gold-plated stainless steel high-pressure crucibles)

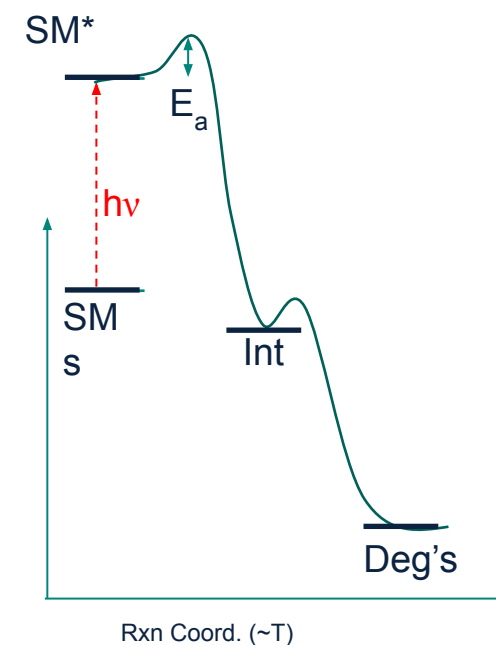
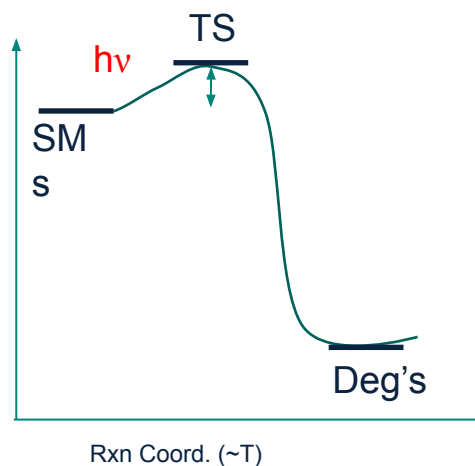
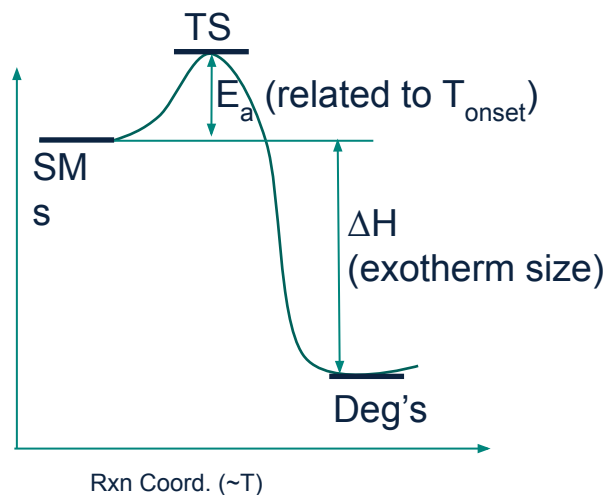


DSC



# Justification for Photocalorimetry

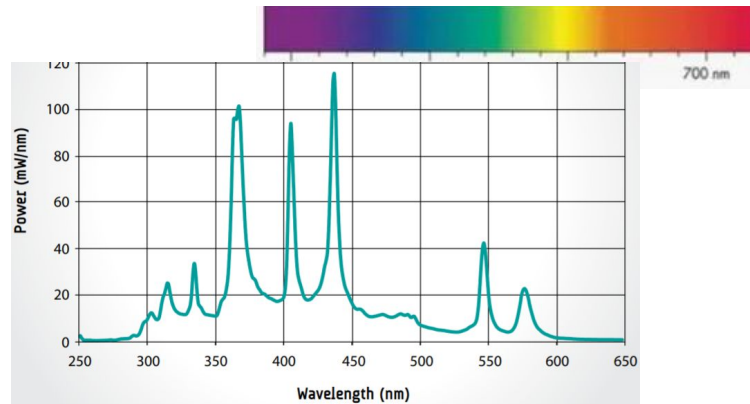
- Want to characterize magnitude and onset of hazardous exotherms in the presence of the **same photons** that will be used during a photochemical process



- $\Delta H$  may change, and **onset T could change significantly** if the degradation pathway and/or mechanism is enabled by light
- Jacket runaway is still plausible, but also loss of cooling could lead to batch overheating from the light source

# Photocalorimeter Accessory (PCA)

- TA's Photocalorimeter Accessory (PCA) includes a **light source** (Excelitas Omnicure S2000) and **adapter** hardware
  - Two parallel light beams, for sample + reference
  - Independent vertical beam adjustment to equalize intensity
  - Max operating temperature  $\sim 250^{\circ}\text{C}$

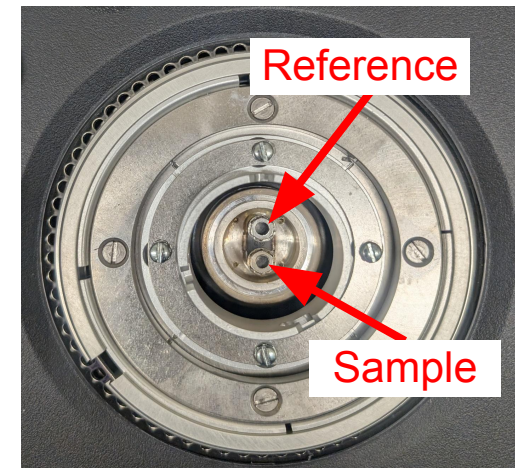


Omnicure S2000 light source output spectrum

- Traditionally, the PCA is used with open DSC pans (e.g., for photo-curing of non-volatile polymers)

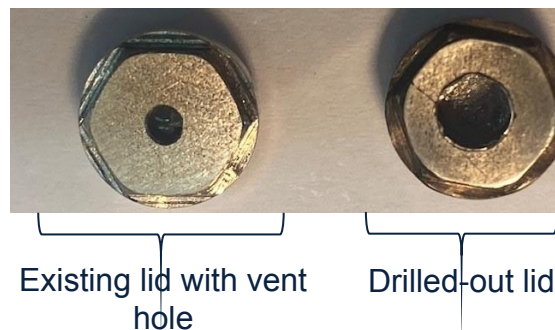


We sought a sealed DSC pan with a transparent "window" to enable irradiation



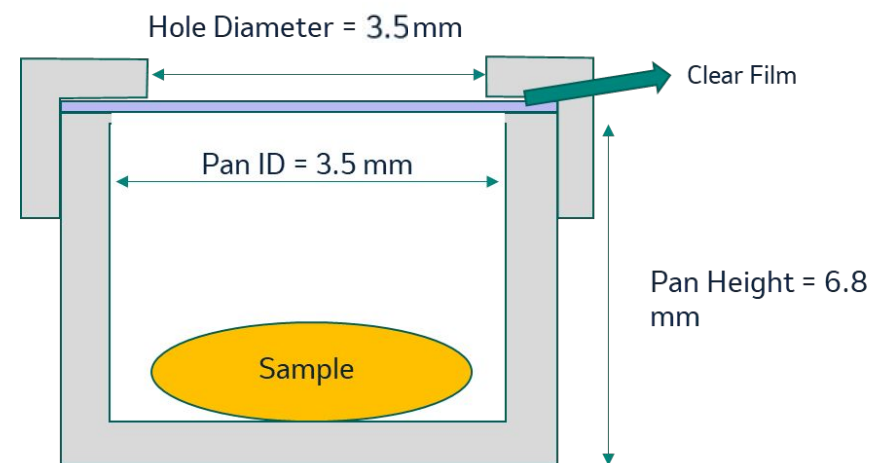
# Crucible Design

- Leveraged existing reusable Tantalum-lined Hastelloy crucibles with screw-down lid and vent hole
  - Drilled hole (~3.5 mm) through existing lid to allow for light penetration
  - Punched-out a transparent disc (“window”) of film to insert inside of lid



## Film options:

- Glass/Sapphire
- Ethylene tetrafluoroethylene (ETFE)
- Fluorinated Ethylene Propylene (FEP)
- Perfluoroalkoxy (PFA)

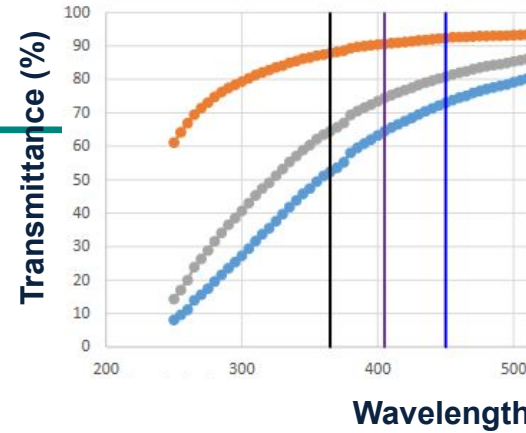


Schematic of photo-DSC Crucible Design

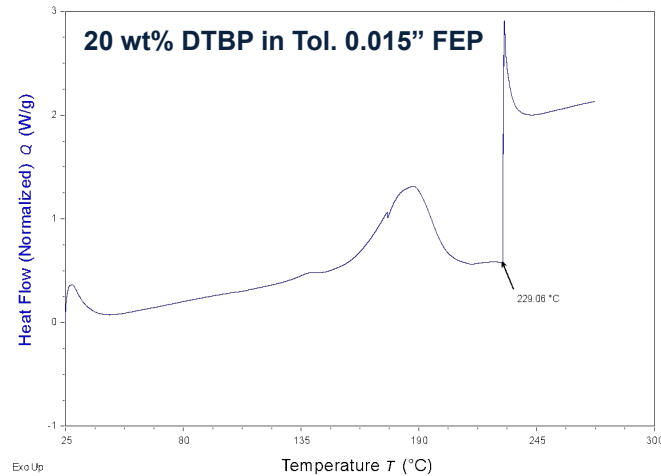
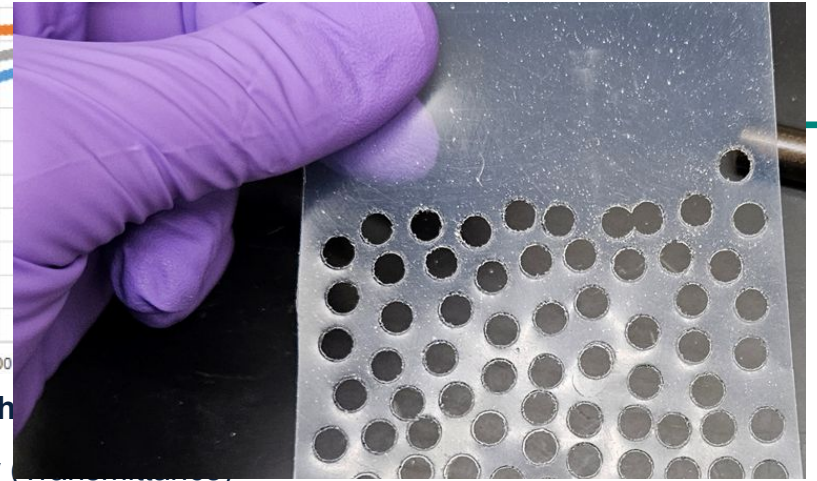
# Window Film Selection

## Key Requirements:

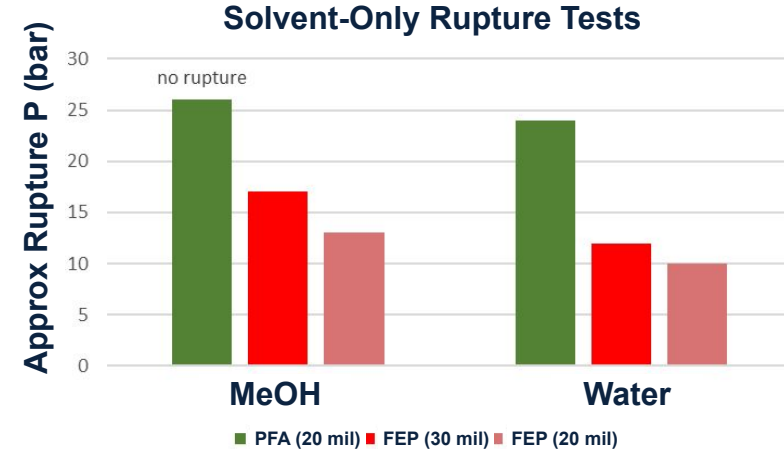
- ✓ Optical transparency
- ✓ Heat resistant (~250°C)
- ✓ Strength (hold pressure)
- ✓ Pliable
- ✓ Easy to manipulate/install
- ✓ Non-reactive
- ✓ Inexpensive



Optical Transparency for PFA and FEP Films



Ruptured PFA film



**20 mil PFA** was selected as the best balance of UV transparency and strength



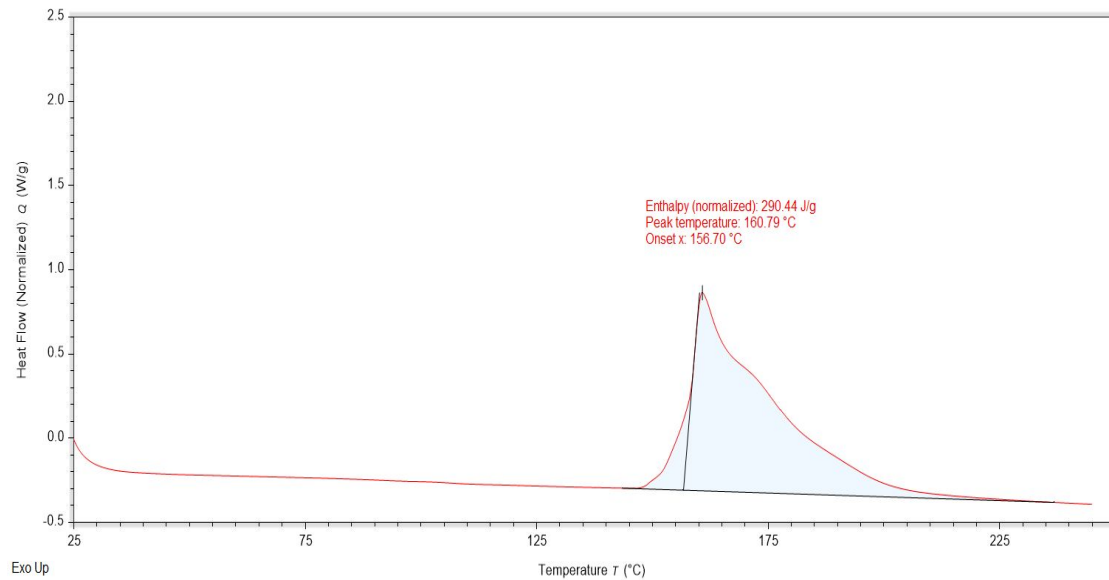
# Proof-of-Concept Data

# UV-Curing Resin w/ PFA window

## No light (temp. ramp)

- Enthalpy: ~300 J/g
- Initiates at ~144 °C

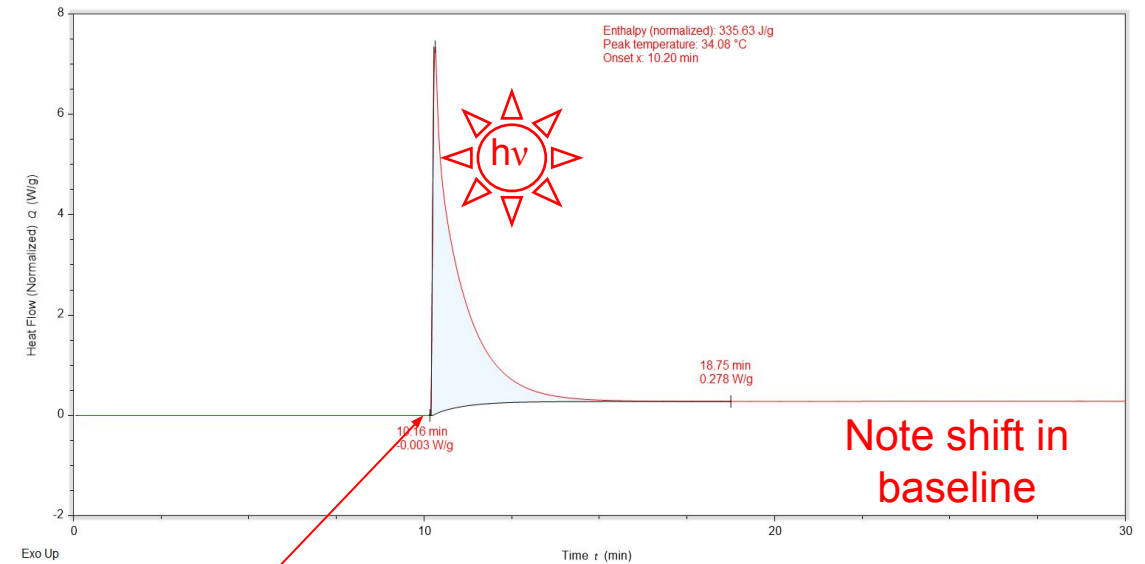
UV curable resin 20mil PFA in hex bomb (no light)



## Light on (UV curing, isothermal)

- Enthalpy: ~300 J/g
- Initiates upon illumination

UV curable resin 20mil PFA in hex bomb (light 75%)



Light source  
turned ON

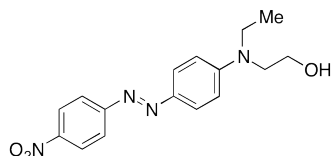
# Searching for Test Cases...

- Criteria:

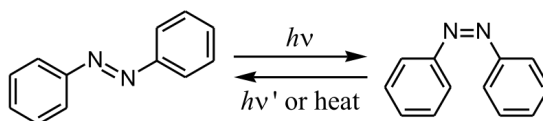
- ✓ Commercially-available molecules with known UV-absorbance
- ✓ Known or suspected to be energetic (need a DSC signal)
- ✓ Neat or in solution (DMSO, Cyrene used as solvents – low volatility, high decomp. energy)

- Candidates

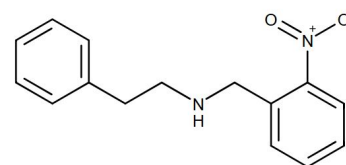
- Azo, nitro dyes



- Azobenzene “photoswitches”

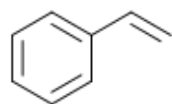


- Photolabile protecting groups (o-nitrobenzyl)

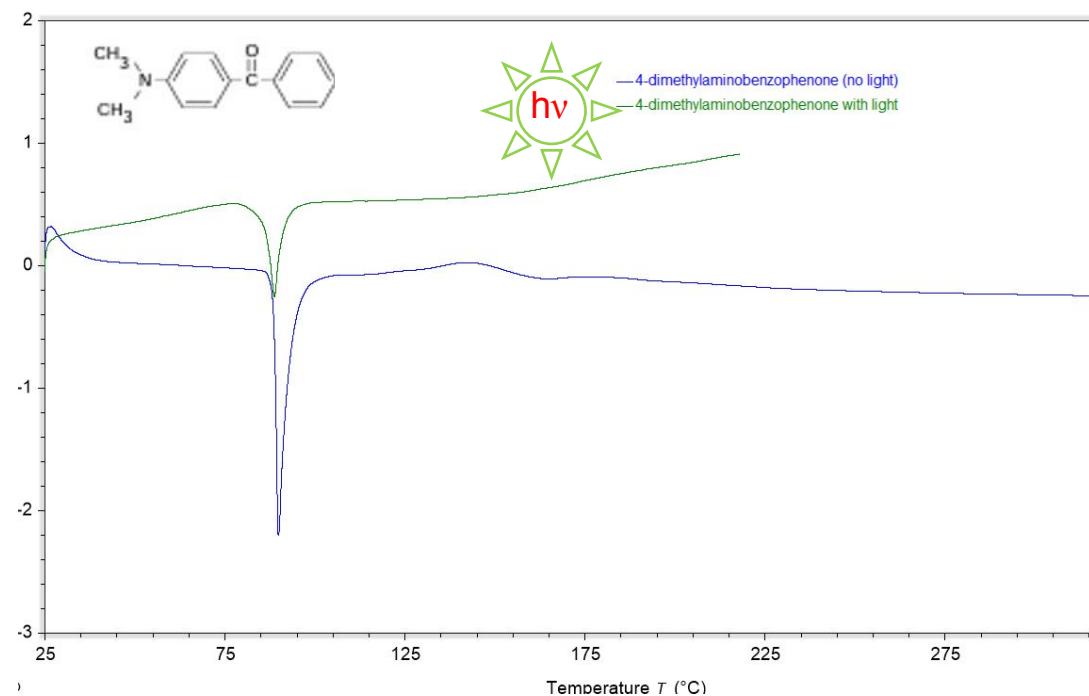
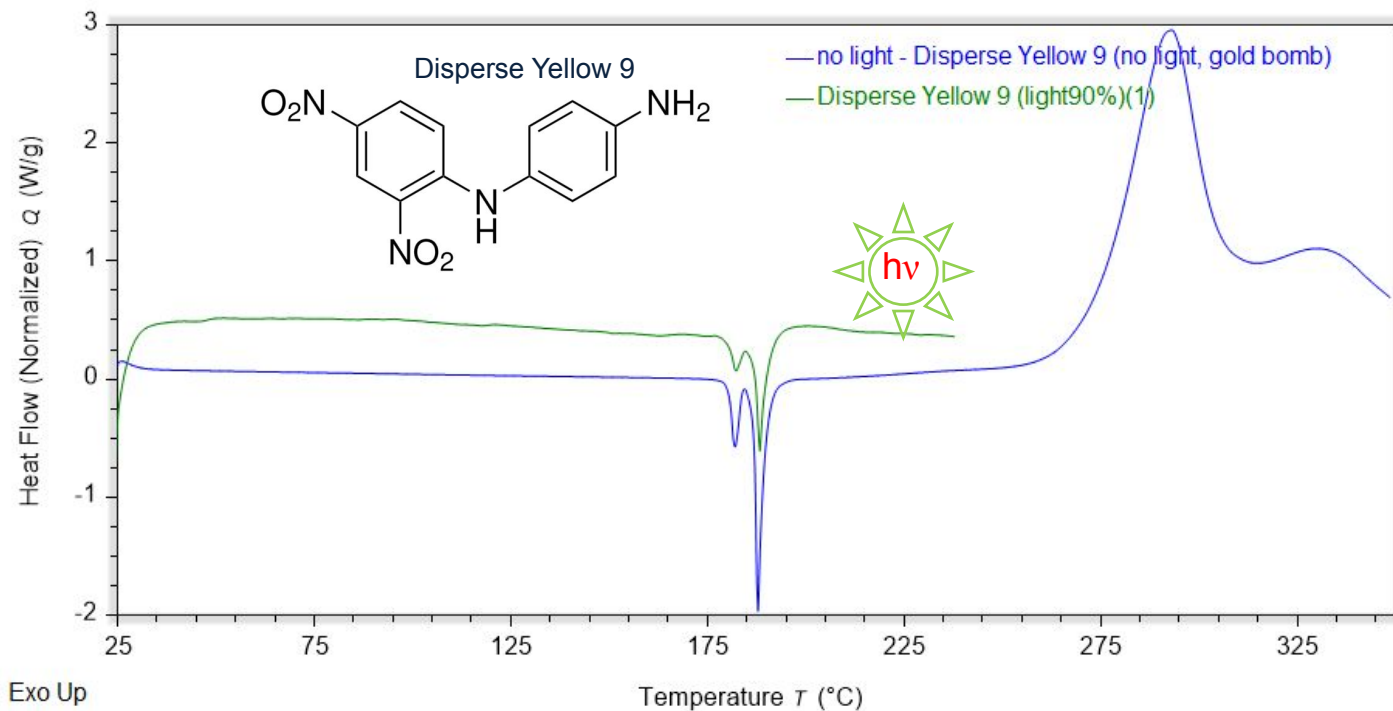


- Diazo photo-initiators

- Photosensitive monomers



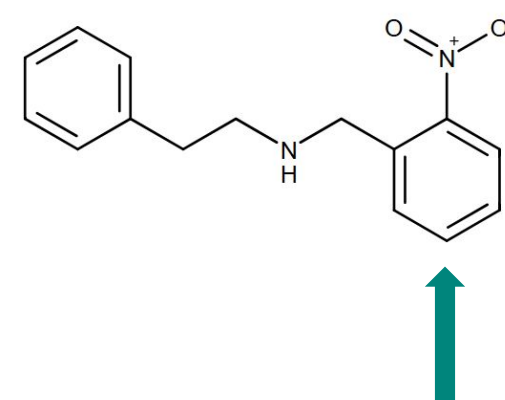
# Results vs. M20 gold crucibles



- Generally good thermograms
- Baseline not quite as smooth/level
- Larger sample size typically used (5-10mg) to improve signal/noise
- Cannot exceed 250°C (limited by both PCA and film max temp)

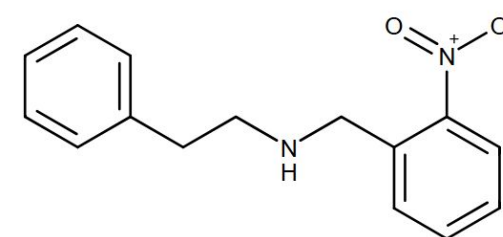
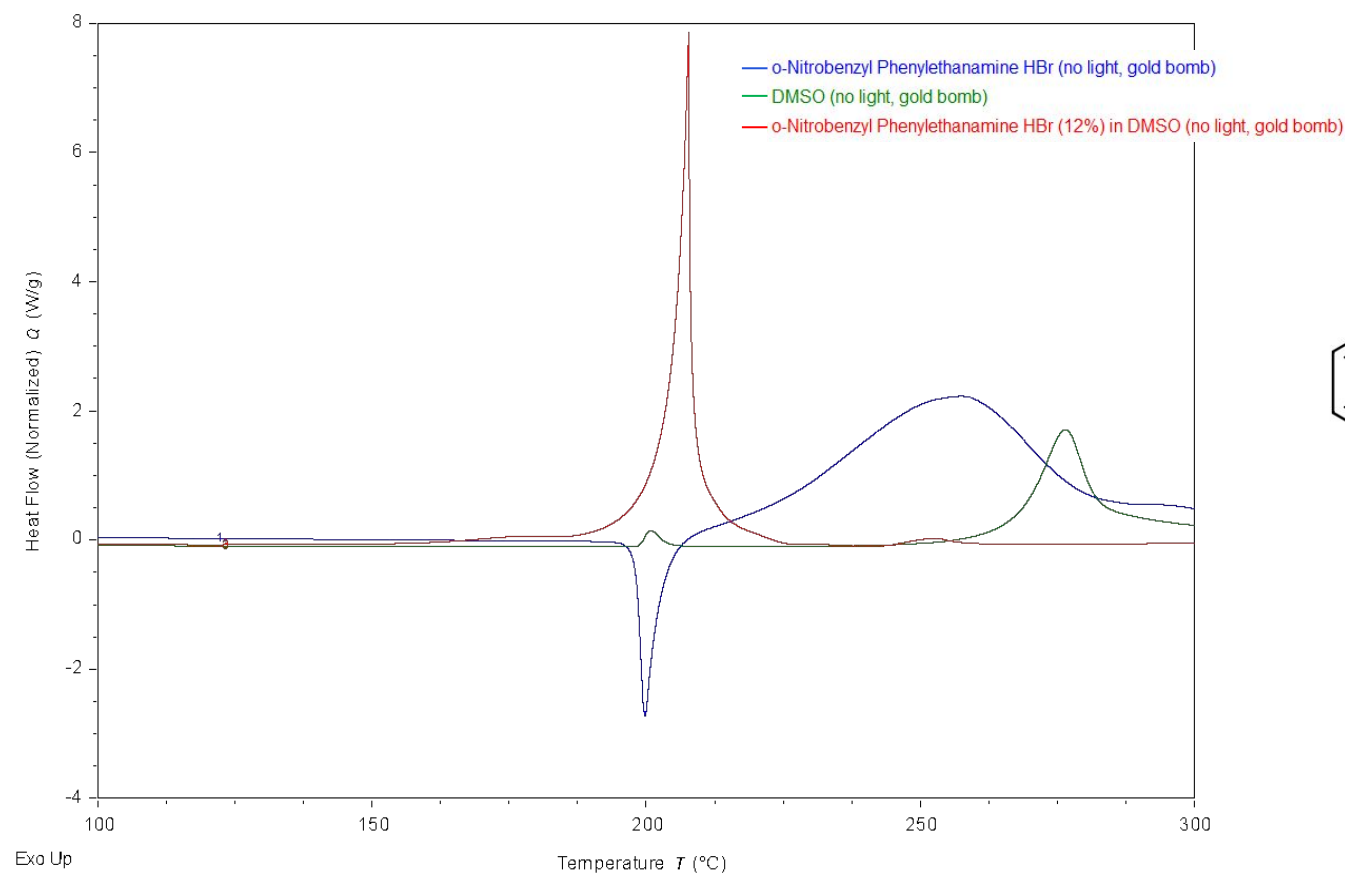
# N-(2-nitrobenzyl)-2-phenylethanamine HBr

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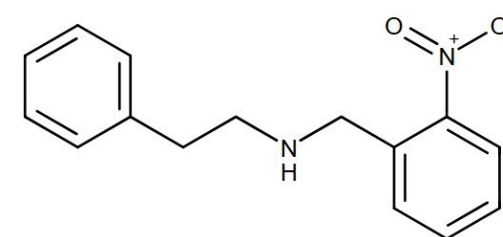
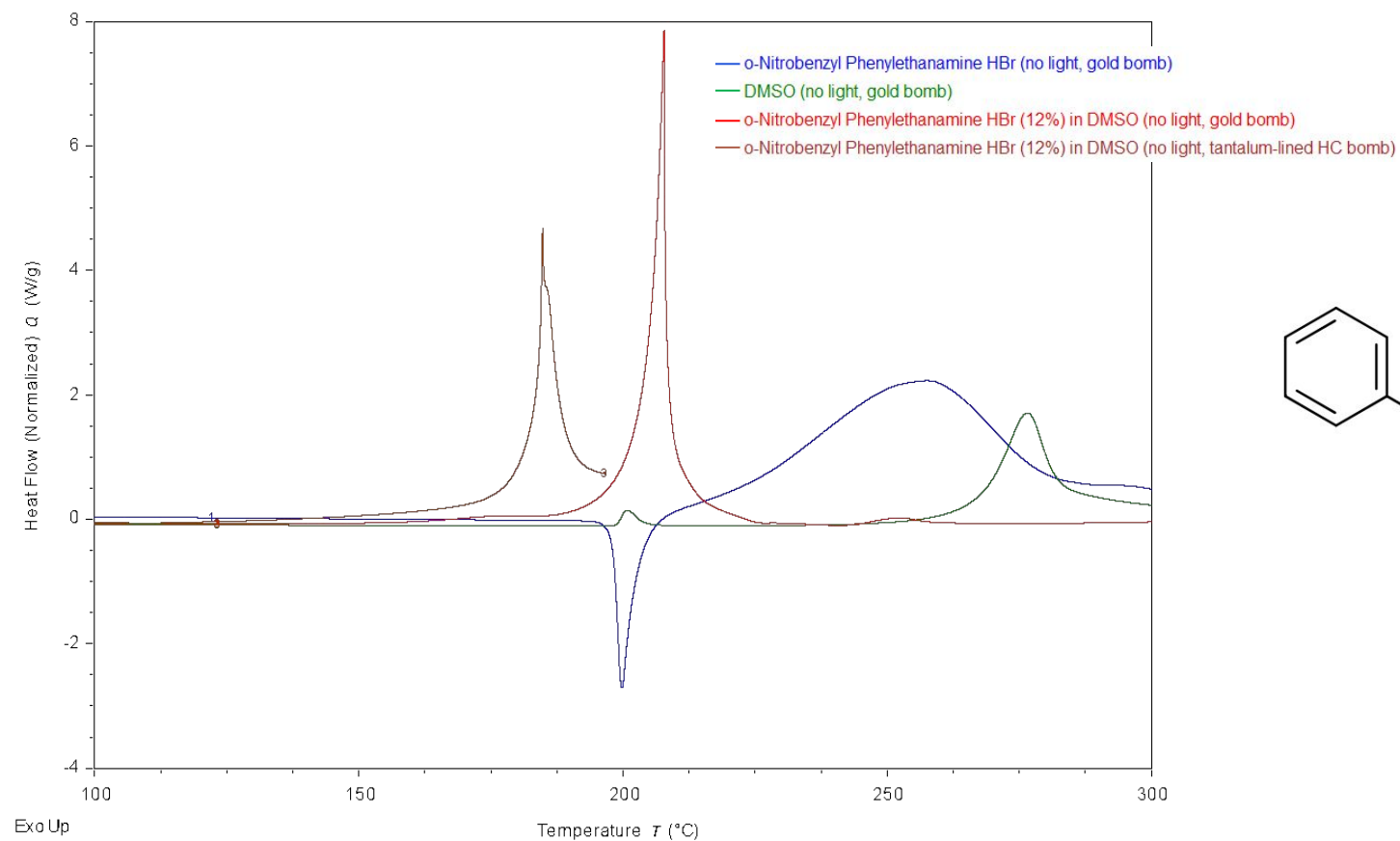


**O-nitrobenzyl** is commonly used as a photolabile protecting group

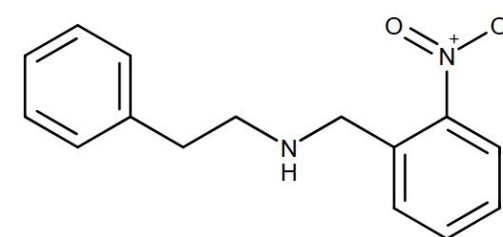
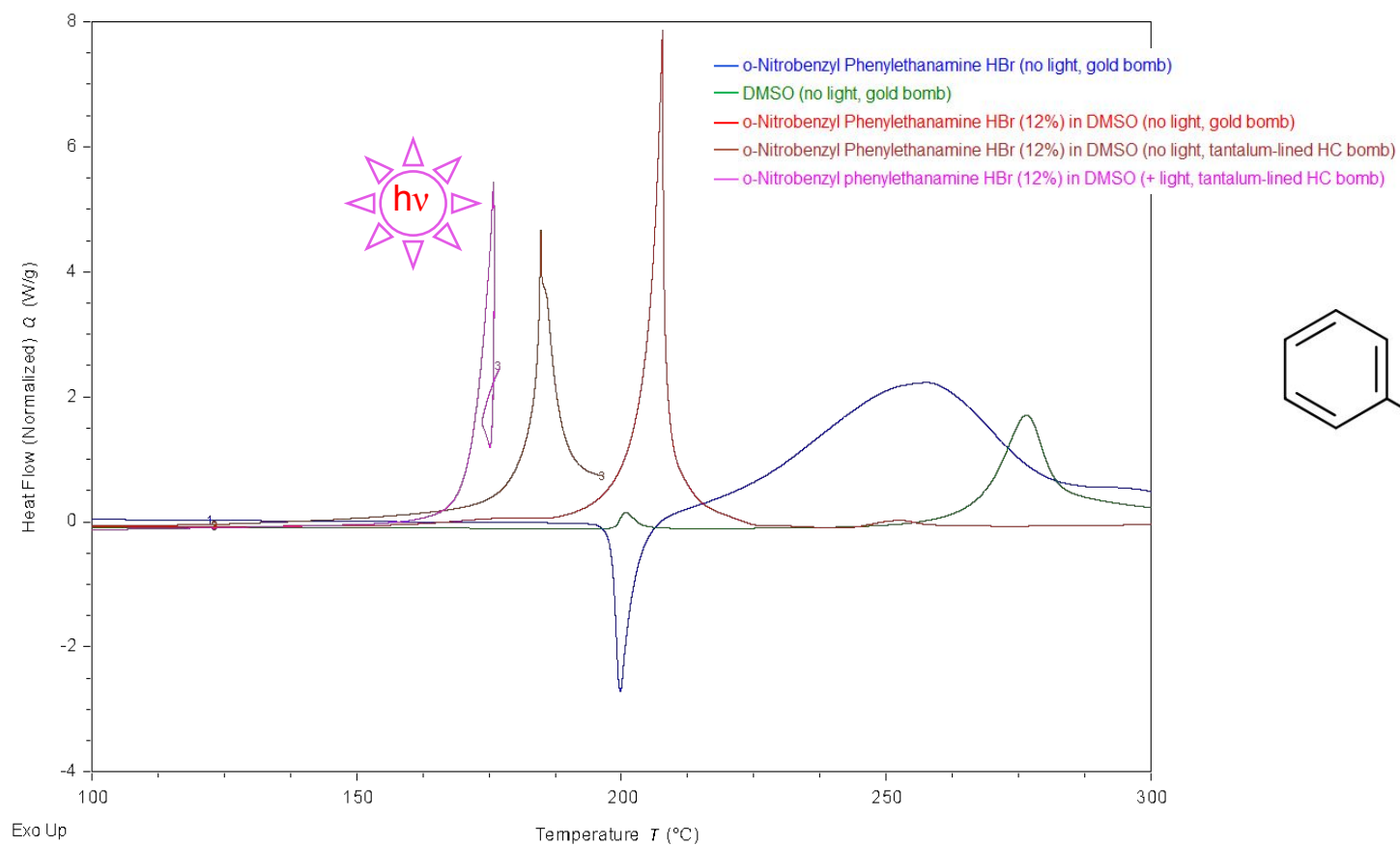
# N-(2-nitrobenzyl)-2-phenylethanamine HBr in DMSO



# N-(2-nitrobenzyl)-2-phenylethanamine HBr in DMSO

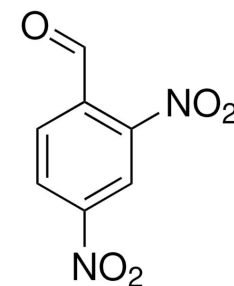


# N-(2-nitrobenzyl)-2-phenylethanamine HBr in DMSO

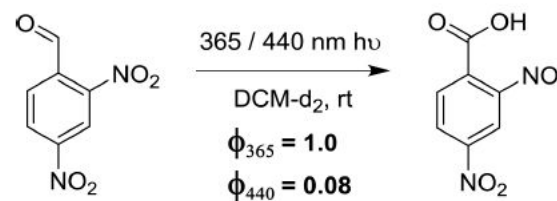


# 2,4-Dinitrobenzaldehyde

Used as actinometer for photo-NMR at Merck



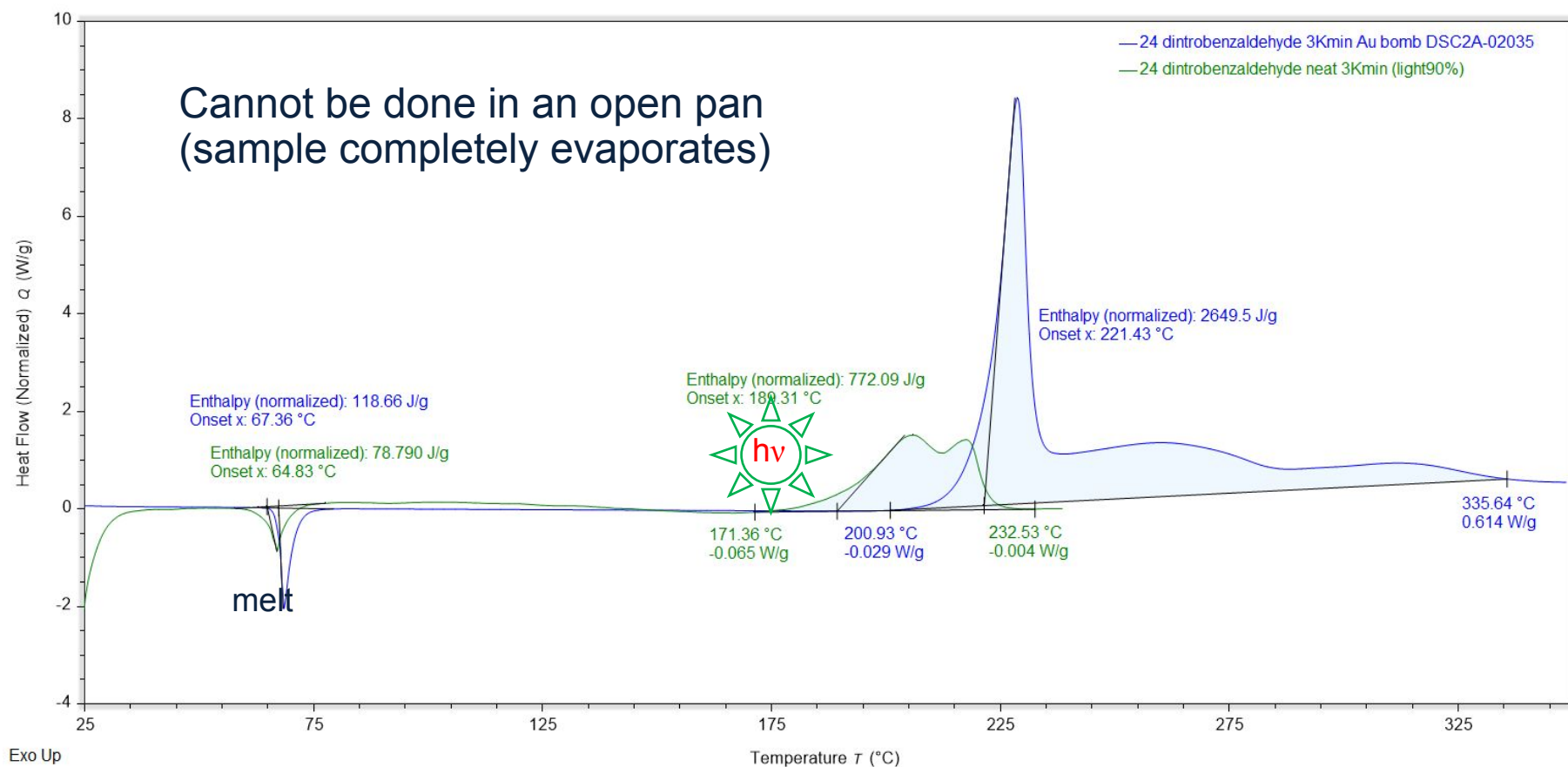
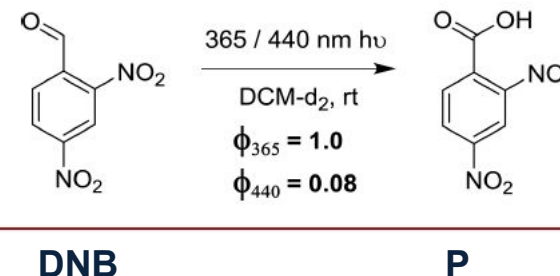
Scheme 3. Photochemistry of 2,4-Dinitrobenzaldehyde



# 2,4-dinitrobenzaldehyde

Neat,  
3K/min

Scheme 3. Photochemistry of 2,4-Dinitrobenzaldehyde



# Conclusions/Future Direction

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- **Conclusions/Summary**

- Demonstrated proof-of-concept, instrument and technique are sufficient to get meaningful data at relevant wavelengths and photon fluxes
- Pressure and Temperature are known limitations, but still suitable for our needs

- **Future Directions**

- Building larger data set, more repeats, understand variability
- Start using photo-DSC for real reactions
  - First “real” reaction stream was analyzed in March (C-N photoredox coupling)
  - Intern this summer will be working on other reactions/applications
- Manuscript is in progress

- **Key Message**

- The field of chemistry is constantly changing. Process safety assessment techniques must evolve to keep up!



# Acknowledgements

Dan Muzzio

Don Bachert

Tao Chen

Ralph Zhao

Francois Levesque

Dan Lehnherr